



IN THE

UNITED STATES PATENT AND TRADEMARK OFFICE

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EXAMINER: Mr. Kiet Nguyen

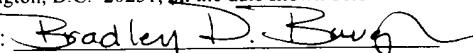
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Dated: March 22, 2002

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COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

AMENDMENT A

Dear Sir:

This amendment is in response to the Office Action mailed October 22, 2001, which established a shortened statutory period for response that expired on January 22, 2002. A fee for a two-month extension of time is included herewith.

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